



US007115185B1

(12) **United States Patent**
Gonzalez et al.

(10) **Patent No.:** **US 7,115,185 B1**
(45) **Date of Patent:** **Oct. 3, 2006**

(54) **PULSED EXCITATION OF INDUCTIVELY COUPLED PLASMA SOURCES**

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(*) Notice: Subject to any disclaimer, the term of this patent is extended or adjusted under 35 U.S.C. 154(b) by 74 days.

(21) Appl. No.: **10/663,104**

(22) Filed: **Sep. 16, 2003**

(51) **Int. Cl.**
C23F 1/02 (2006.01)
C23C 16/00 (2006.01)
H01J 7/24 (2006.01)

(52) **U.S. Cl.** **156/345.44**; 156/345.48;
118/723 R; 118/723 I; 315/111.41

(58) **Field of Classification Search** 156/345;
118/723; 315/111

See application file for complete search history.

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(57) **ABSTRACT**

The reaction rate of a feed gas flowed into a plasma chamber is controlled. In one embodiment a pulsed power supply repeatedly applies a high power pulse to the plasma chamber to increase the reaction rate of plasma within the chamber, and applies a low power pulse between applications of the high power pulses.

28 Claims, 8 Drawing Sheets

